

Atty. Docket No. 2002-0039-06  
USSN 10/712,688

In the Specification:

On Page 5, line 14, please insert the following:

**--BRIEF DESCRIPTION OF THE DRAWINGS**

FIG. 1 is a layout of a lithography laser system with a beam delivery unit.

FIGS. 2, 2A and 2B show features of a pulse stretching unit.

FIGS. 3A, 3B, 3C, 3D, 3E, 3F and 3G show features of a relay optics for the FIG. 1 laser system.

FIGS. 4A, 4B and 4C show beam delivery configurations.

FIG. 5 is a graph of pulse energy versus charging voltage.

FIG. 6 shows a technique of tuning a beam 90 degrees with prisms.

FIG. 7 shows a laser light source with beam delivery to a scanner.

FIGS. 8A-8E shows an easily sealing bellows seal.

FIG. 9 demonstrates a feature of a preferred pulse stretcher.--

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On page 21, please amend the second paragraph as follows:

For example, although the invention, including the utilization of a beam delivery unit, is described using a MOPA laser configuration, a single chamber laser system such as described in U.S. Patent No. 6,730,261 ~~6,330,261~~ could be utilized. For lithography either ArF, KrF or F<sub>2</sub> systems could be utilized. This invention may also be applied to uses other than lithography in which other ultraviolet wavelength may be more appropriate. An important improvement here is the addition of equipment to a laser system to deliver an ultraviolet laser beam having desire beam qualities to an input port of a equipment needing an ultraviolet laser light source. Various feedback control arrangements other than those referred to herein could be used.